

FIG. 1

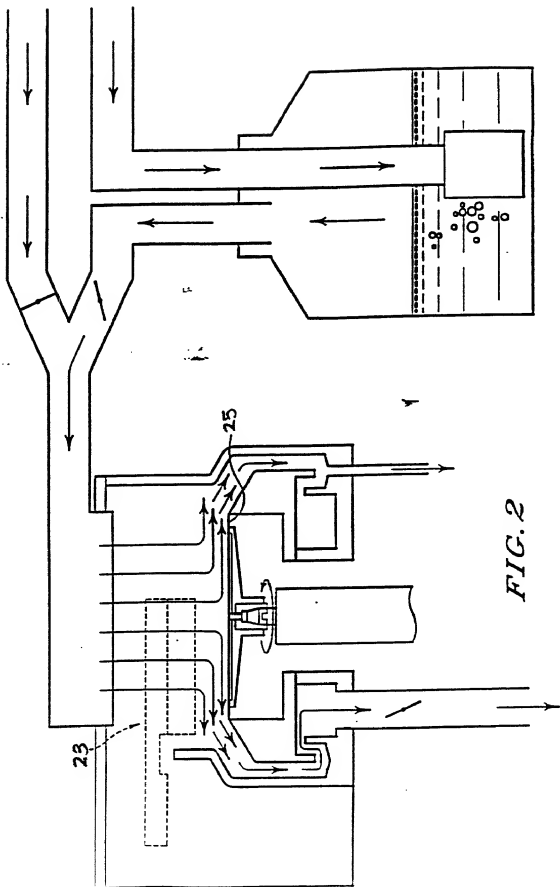


FIG. 2

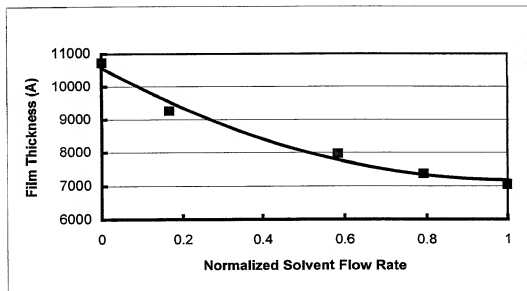


Figure 3a) Mean resist film thickness as a function of solvent concentration at a fixed drying spin speed . Mean film thickness can be varied close to 4000Å by varying the solvent concentration at a fixed 2000 rpm.

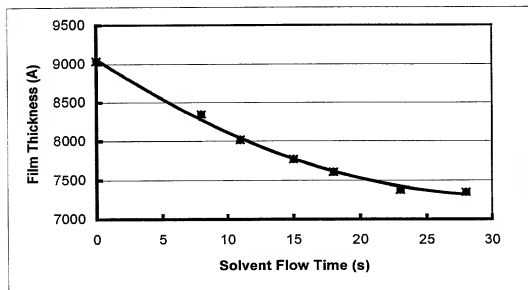
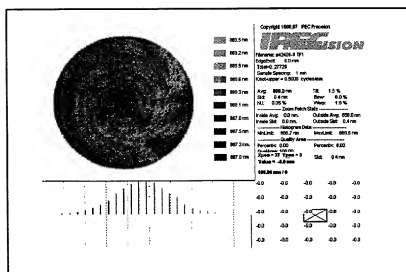


Figure 3b): Film thickness as a function of solvent flow time for a working example.



Conventional Coater

Film Thickness (Å)

Wafer Position (mm)

Legend:

- Nominal
- + 1.0 C
- 1.0 C

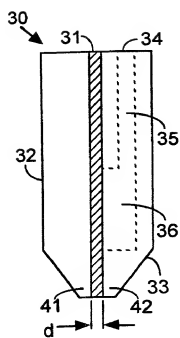


FIG. 8

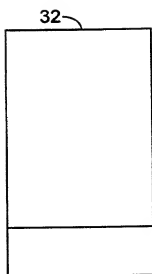


FIG. 9

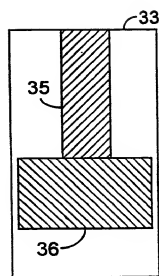


FIG. 10

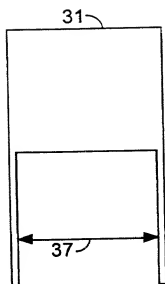


FIG. 11

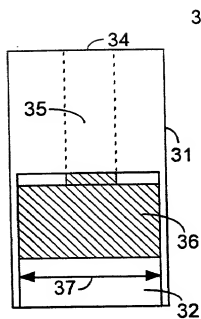


FIG. 12

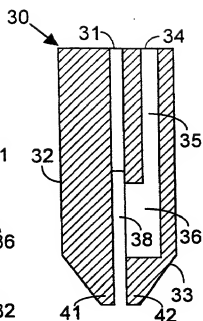


FIG. 13

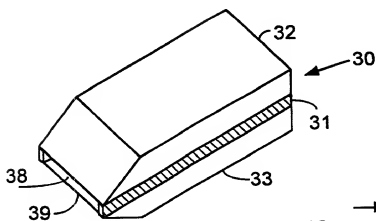


FIG. 14

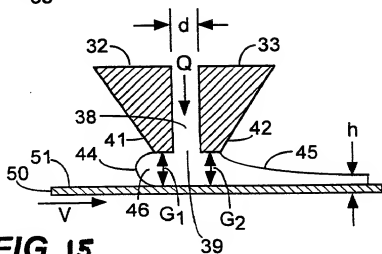


FIG. 15

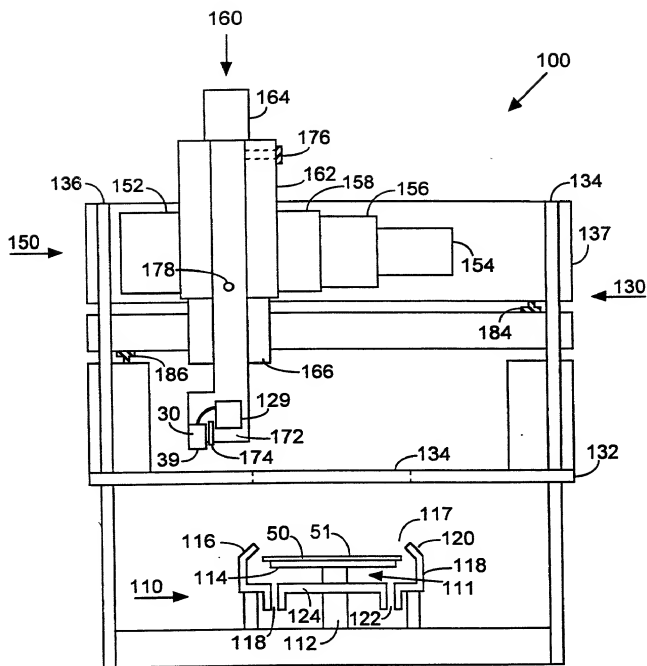
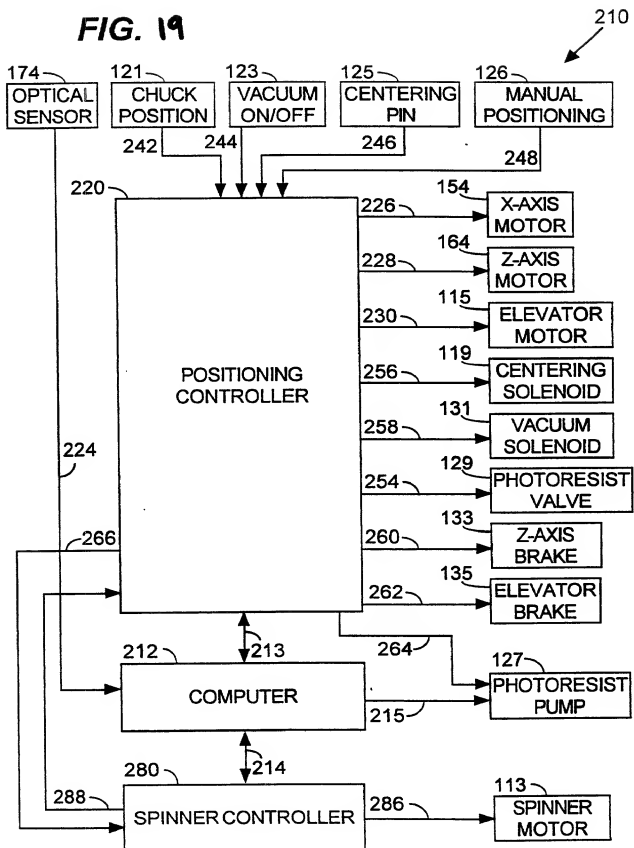


FIG. 16

FIG. 19



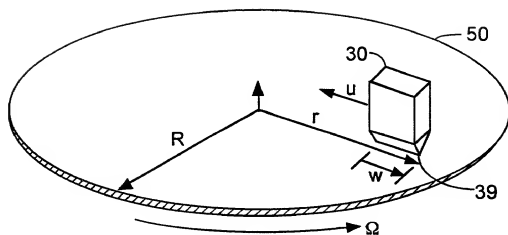


FIG. 24

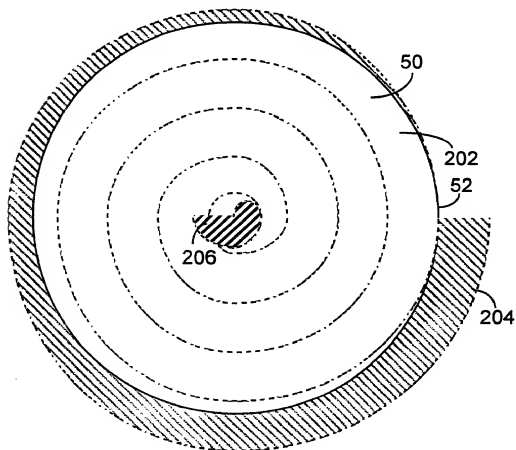


FIG. 25